

L Number	Hits	Search Text	DB	Time stamp
6	9	((("20030096189") or ("6383713") or ("6291130") or ("5856561")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/18 14:42
-	1	("20020150834").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:25
-	3086104	resin binder polymer resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:25
-	15856	(photoacid acid (photo adj acid)) near generat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:26
-	2055	acetal near moiety) (acetal near compound	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 08:53
-	197	(resin binder polymer resist photoresist) and ((photoacid acid (photo adj acid)) near generat\$3) and (acetal near moiety) (acetal near compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 10:41
-	275472	acrylate methacrylate cycloolefin	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:31
-	24	(2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:33
-	16008	gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:16
-	146	(acrylate methacrylate cycloolefin) and ((resin binder polymer resist photoresist) and ((photoacid acid (photo adj acid)) near generat\$3) and (acetal near moiety) (acetal near compound))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:34
-	24	(\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:15
-	24	(\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:10
-	24	((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) (((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:29
-	14	((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) (((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:27

-	24	((("2003082926") or ("2002150834") or ("2002081523") or ("6548221") or ("2000482359") or ("2002051933") or ("6492091") or ("2002102491") or ("6383713") or ("6348297") or ("6239231")).PN.) ((((((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)) and ((acrylate methacrylate cycloolefin) and ((resin binder polymer resist photoresist) and ((photoacid acid (photo adj acid)) near generat\$3) and (acetal near moiety) (acetal near compound)))) (((((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)) and ((resin binder polymer resist photoresist) and ((photoacid acid (photo adj acid)) near generat\$3) and (acetal near moiety) (acetal near compound)))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 16:23
-	2055	acetal near moiety) (acetal near compound	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 09:05
-	2055	acetal near moiety) (acetal near compound	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 09:37
-	1377	yAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 17:56
-	2	(yAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI) and (acetal near moiety) (acetal near compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 10:03
-	0	20020150834.URPN.	USPAT	2003/06/11 10:03
-	44	(yAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI) and (photoresist resist) and (\$5acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 11:19
-	6	(US-6517991-\$ or US-6291130-\$ or US-6548221-\$).did. or (US-20020150834-\$ or US-20030044718-\$).did. or (JP-2002311587-\$).did.	USPAT; US-PGPUB; JPO	2003/06/11 10:04

-	43	((YAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI) and (photoresist resist) and (\$5acid near generat\$3)) not ((US-6517991-\$ or US-6291130-\$ or US-6548221-\$).did. or (US-20020150834-\$ or US-20030044718-\$).did. or (JP-2002311587-\$).did.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 10:09
-	18633	(acetal) same (additive (dissolution adj inhibitor) compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 10:43
-	5	((acetal) same (additive (dissolution adj inhibitor) compound)) and (((YAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI) and (photoresist resist) and (\$5acid near generat\$3)) not ((US-6517991-\$ or US-6291130-\$ or US-6548221-\$).did. or (US-20020150834-\$ or US-20030044718-\$).did. or (JP-2002311587-\$).did.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 10:46
-	1477	lactone same acetal	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 10:48
-	444	((acetal) same (additive (dissolution adj inhibitor) compound)) and (photoresist resist) and (\$5acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 12:35
-	1	di-t-butoxyacetyl adj bisphenol adj "A"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 12:36
-	5140	(acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:09
-	141586	acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:26
-	2482	((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:26
-	564	((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf) and (430/270.1.ccls.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:41
-	14	((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:28

-	7	(((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:29
-	0	20030073030.URPN.	USPAT	2003/06/11 15:30
-	14718	\$5acid near generat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:40
-	485	(((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:40
-	484790	acrylic acrylate methacrylate methacrylic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:41
-	426	(((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:41
-	253	"153" and (430/270.1.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:41
-	426	(((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic)) and (430/270.1.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:44
-	373	((((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic)) and (430/270.1.ccls.)) and ((resist binder photoresist resin) near composition)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:48

-	367	<p>((((((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic)) and (430/270.1.ccls.)) and ((resist binder photoresist resin) near composition)) not (((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((3-methyladamantyl adj methacrylate) (3-methyl adj adamantyl adj methacrylate)) (((3-methyladamantyl adj methacrylate) (3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone))))</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:48
-	9	<p>((((((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic)) and (430/270.1.ccls.)) and ((resist binder photoresist resin) near composition)) not (((((acid adj (labile cleavable cleve dissociable)) (acid near eliminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((3-methyladamantyl adj methacrylate) (3-methyl adj adamantyl adj methacrylate)) (((3-methyladamantyl adj methacrylate) (3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)))) and "drri1"</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 17:29

133	(((((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic)) and (430/270.1.ccls.)) and ((resist binder photoresist resin) near composition)) not (((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) (\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) (\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)))) and (dissolution adj inhibitor)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 17:30
8819	gamma-butyrolactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/12 11:50
373305	pattern\$3 same (underlying) same (resist photoresist) saem (mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/12 13:34
44827	(pattern\$3 same (underlying) same (resist photoresist) saem (mask)) same (conventional well-known well adj known)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/12 13:36
504	((pattern\$3 same (underlying) same (resist photoresist) saem (mask)) same (conventional well-known well adj known)) and (430/270.1.ccls.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/12 13:36
374	((pattern\$3 same (underlying) same (resist photoresist) saem (mask)) same (conventional well-known well adj known)) and (430/270.1.ccls.)) and (semiconductor semi-conductor VLSI LSI micropatterning mircofabrication)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/12 13:43
276	((pattern\$3 same (underlying) same (resist photoresist) saem (mask)) same (conventional well-known well adj known)) and (430/270.1.ccls.)) and (semiconductor semi-conductor VLSI LSI micropatterning mircofabrication)	USPAT	2003/06/12 13:43
1	("6673511").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 10:47
5	((("20030232273") or ("6369181") or ("6013411"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:09
37	(\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:15
17746	gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:16

-	23	(((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:16
-	6	(((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) same (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:17
-	1	("6673511").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 14:00
-	1674	acetal same lactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 13:30
-	88	acetal same gamma-butyrolactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 13:48
-	5	((("4996121") or ("6495310") or ("6387595") or ("6541183") or ("6660445"))).PN.	USPAT	2004/02/16 13:51
-	362	benzyl same (acid adj labile)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 14:01
-	1	("6383713").PN.	USPAT	2004/02/16 17:36
-	246	(acetal adj moiety)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 17:37
-	159212	acid near5 (eliminat\$3 remov\$3 labile cleav\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 17:38
-	17	((acetal adj moiety)) same (acid near5 (eliminat\$3 remov\$3 labile cleav\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 17:39
-	0	20020150834.URPN.	USPAT	2004/02/16 17:47
-	1460	yAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 17:56
-	147	(yAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI) AND (RESIST PHOTORESIST)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 17:57
-	20	((yAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI TAKECHI-SATOSHI-C-O-FUJITSU-LI) AND (RESIST PHOTORESIST)) AND ((ACID PHOTOACID) NEAR GENERATOR)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/16 17:57

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L1 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\09940665-2.str

L2 STRUCTURE UPLOADED

=> que L2 AND L1

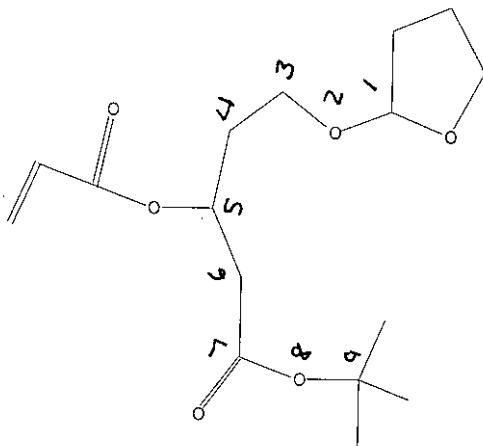
L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 2067

L2 STR



G1

Structure attributes must be viewed using STN Express query preparation.
L3 QUE ABB=ON PLU=ON L2 AND L1

=> s l3 sss sam

SAMPLE SEARCH INITIATED 13:40:45 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 0 TO ITERATE

100.0% PROCESSED 0 ITERATIONS
SEARCH TIME: 00.00.01

0 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 0 TO 0
PROJECTED ANSWERS: 0 TO 0

L4 0 SEA SSS SAM L2 AND L1

=> FIL CAPLUS, USPATFULL, HCAPLUS
COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
0.42	0.63

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 13:40:50 ON 16 FEB 2004
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=> s l4

L5 0 L4

=> file reg
COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
4.15	4.78

FULL ESTIMATED COST

FILE 'REGISTRY' ENTERED AT 13:41:10 ON 16 FEB 2004
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DICTIONARY FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9

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to the file summary sheet on the web at:
<http://www.cas.org/ONLINE/DBSS/registryss.html>

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L6 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\09940665-3.str

L7 STRUCTURE UPLOADED

=> que L7 AND L6

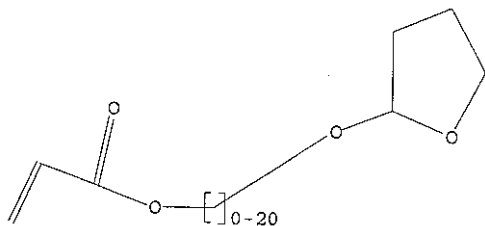
L8 QUE L7 AND L6

=> d

L8 HAS NO ANSWERS

L6 SCR 2067

L7 STR



G1

Structure attributes must be viewed using STN Express query preparation.
L8 QUE ABB=ON PLU=ON L7 AND L6

=> s l8 sss sam

SAMPLE SEARCH INITIATED 13:42:51 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 20 TO ITERATE

100.0% PROCESSED 20 ITERATIONS

1 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**

PROJECTED ITERATIONS: 132 TO 668

PROJECTED ANSWERS: 1 TO 80

L9 1 SEA SSS SAM L7 AND L6

=> FIL CAPLUS, USPATFULL, HCAPLUS
COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
1.26	6.04

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 13:42:57 ON 16 FEB 2004
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FILE 'USPATFULL' ENTERED AT 13:42:57 ON 16 FEB 2004
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=> s 19
L10

5 L9

=> duplicates remove 110
DUPLICATE PREFERENCE IS 'CAPLUS, USPATFULL, HCAPLUS'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L10
L11 3 DUPLICATE REMOVE L10 (2 DUPLICATES REMOVED)

=> d 111 1-3 ibib hitstr

L11 ANSWER 1 OF 3 USPATFULL on STN
ACCESSION NUMBER: 91:17029 USPATFULL
TITLE: Electrophotographic lithographic printing plate
precursor containing resin having hydroxy group forming
functional group
INVENTOR(S): Kato, Eiichi, Shizuoka, Japan
Ishii, Kazuo, Shizuoka, Japan
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, Japan (non-U.S.
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 4996121		19910226
APPLICATION INFO.:	US 1989-293400		19890104 (7)

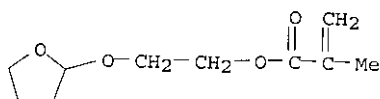
	NUMBER	DATE
PRIORITY INFORMATION:	JP 1988-265	19880106
	JP 1988-14577	19880127
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	Granted	
PRIMARY EXAMINER:	McCamish, Marion C.	
ASSISTANT EXAMINER:	RoDee, Christopher D.	
LEGAL REPRESENTATIVE:	Sughrue, Mion, Zinn, Macpeak & Seas	
NUMBER OF CLAIMS:	10	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1200	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 124660-88-4
(electrophotog. plate with photoconductive layer containing, for lithog.
plate fabrication)
RN 124660-88-4 USPATFULL
CN 2-Propenoic acid, 2-methyl-, ethyl ester, polymer with 4-hydroxybutyl
2-methyl-2-propenoate and 2-[(tetrahydro-2-furanyl)oxy]ethyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

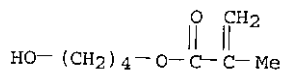
CM 1

CRN 121462-74-6
CMF C10 H16 O4



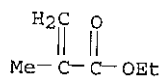
CM 2

CRN 997-46-6
CMF C8 H14 O3



CM 3

CRN 97-63-2
CMF C6 H10 O2

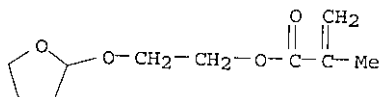


L11 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1
 ACCESSION NUMBER: 1990:468420 CAPLUS
 DOCUMENT NUMBER: 113:68420
 TITLE: Direct-imaging lithographic original plate having
 image-receiving layer with binder containing protected
 hydroxy-substituted polymer and hardener
 INVENTOR(S): Kato, Eiichi; Ishii, Kazuo
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 01271292	A2	19891030	JP 1988-100192	19880425
PRIORITY APPLN. INFO.: JP 1988-100192 19880425				
IT 124660-88-4				
RL: USES (Uses)				
(binder, for image-receiving layer, for direct-imaging lithog. plate, hydrophilicity associated with oil-based ink affinity in)				
RN 124660-88-4	CAPLUS			
CN	2-Propenoic acid, 2-methyl-, ethyl ester, polymer with 4-hydroxybutyl 2-methyl-2-propenoate and 2-[(tetrahydro-2-furanyl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)			

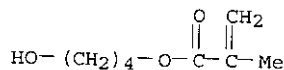
CM 1

CRN 121462-74-6
CMF C10 H16 O4



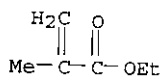
CM 2

CRN 997-46-6
CMF C8 H14 O3



CM 3

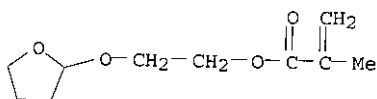
CRN 97-63-2
CMF C6 H10 O2



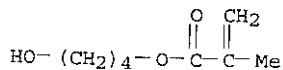
L11 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2
 ACCESSION NUMBER: 1990:601290 CAPLUS
 DOCUMENT NUMBER: 113:201290
 TITLE: Electrophotographic lithographic printing plate precursor
 INVENTOR(S): Kato, Eiichi; Ishii, Kazuo
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Eur. Pat. Appl., 43 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 323854	A2	19890712	EP 1989-100179	19890105
EP 323854	A3	19910703		
R: DE, GB				
JP 01179052	A2	19890717	JP 1988-265	19880106
JP 01191158	A2	19890801	JP 1988-14577	19880127
US 4996121	A	19910226	US 1989-293400	19890104
PRIORITY APPLN. INFO.:			JP 1988-265	19880106
			JP 1988-14577	19880127

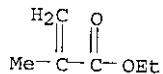
IT 124660-88-4
 RL: USES (Uses)
 (electrophotog. plate with photoconductive layer containing, for lithog. plate fabrication)
 RN 124660-88-4 CAPLUS
 CN 2-Propenoic acid, 2-methyl-, ethyl ester, polymer with 4-hydroxybutyl 2-methyl-2-propenoate and 2-[(tetrahydro-2-furanyl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)
 CM 1
 CRN 121462-74-6
 CMF C10 H16 O4



CM 2
 CRN 997-46-6
 CMF C8 H14 O3



CM 3
 CRN 97-63-2
 CMF C6 H10 O2



=>

FULL ESTIMATED COST

15.14

21.18

FILE 'REGISTRY' ENTERED AT 13:43:52 ON 16 FEB 2004
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Property values tagged with IC are from the ZIC/VINITI data file
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STRUCTURE FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9
DICTIONARY FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9

TSCA INFORMATION NOW CURRENT THROUGH JULY 14, 2003

Please note that search-term pricing does apply when
conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more
information enter HELP PROP at an arrow prompt in the file or refer
to the file summary sheet on the web at:
<http://www.cas.org/ONLINE/DBSS/registryss.html>

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L12 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\09940665-4.str

L13 STRUCTURE UPLOADED

=> que L13 AND L12

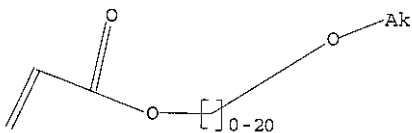
L14 QUE L13 AND L12

=> d

L14 HAS NO ANSWERS

L12 SCR 2067

L13 STR



G1

Structure attributes must be viewed using STN Express query preparation.
L14 QUE ABB=ON PLU=ON L13 AND L12

=> s l14 sss sam

SAMPLE SEARCH INITIATED 13:44:44 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 8008 TO ITERATE

12.5% PROCESSED 1000 ITERATIONS
INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)
SEARCH TIME: 00.00.01

50 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 154798 TO 165522

PROJECTED ANSWERS: 64257 TO 71237

L15 50 SEA SSS SAM L13 AND L12

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L16 SCREEN CREATED

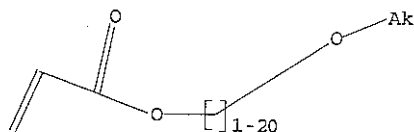
=>
Uploading C:\Program Files\Stnexp\Queries\09940665-5.str

L17 STRUCTURE UPLOADED

=> que L17 AND L16

L18 QUE L17 AND L16

=> d
L18 HAS NO ANSWERS
L16 SCR 2067
L17 STR



G1

Structure attributes must be viewed using STN Express query preparation.
L18 QUE ABB=ON PLU=ON L17 AND L16

=> s l18 sss sam
SAMPLE SEARCH INITIATED 13:45:58 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 8719 TO ITERATE

11.5% PROCESSED 1000 ITERATIONS 50 ANSWERS
INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 168786 TO 179974
PROJECTED ANSWERS: 62982 TO 69894

L19 50 SEA SSS SAM L17 AND L16

=> FIL CAPLUS, USPATFULL, HCAPLUS
COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
1.68	22.86

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 13:46:03 ON 16 FEB 2004
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FILE 'USPATFULL' ENTERED AT 13:46:03 ON 16 FEB 2004
CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'HCAPLUS' ENTERED AT 13:46:03 ON 16 FEB 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
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=> s l19
L20 106 L19

=> s l20 and (resist or photoresist)
L21 5 L20 AND (RESIST OR PHOTORESIST)

=> duplicates remove l21
DUPLICATE PREFERENCE IS 'CAPLUS, USPATFULL, HCAPLUS'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L21
L22 2 DUPLICATE REMOVE L21 (3 DUPLICATES REMOVED)

=> d l22 1-2 ibib hitstr

L22 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2002:556013 CAPLUS
DOCUMENT NUMBER: 137:116960
TITLE: Lithographic plate having conformal overcoat and
photosensitive layer on a rough substrate
INVENTOR(S): Teng, Gary Ganghui
PATENT ASSIGNEE(S): USA

SOURCE: U.S. Pat. Appl. Publ., 10 pp., Cont.-in-part of U.S. Ser. No. 873,598.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 8
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002098447	A1	20020725	US 2002-46789	20020115
US 6495310	B2	20021217		
US 6387595	B1	20020514	US 2000-699784	20001030
US 2003036019	A1	20030220	US 2001-873598	20010604
US 6541183	B2	20030401		

PRIORITY APPLN. INFO.: US 2000-699784 A2 20001030
 US 2001-873598 A2 20010604

IT 443150-29-6P, Ebecryl RX 8301-Sartomer SR 399 copolymer
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (photosensitive layer of lithog. printing plate containing)

RN 443150-29-6 CAPLUS

CN 2-Propenoic acid, 2-[[[3-hydroxy-2,2-bis[[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl ester, polymer with Ebecryl RX 8301 (9CI) (CA INDEX NAME)

CM 1

CRN 344346-13-0

CMF Unspecified

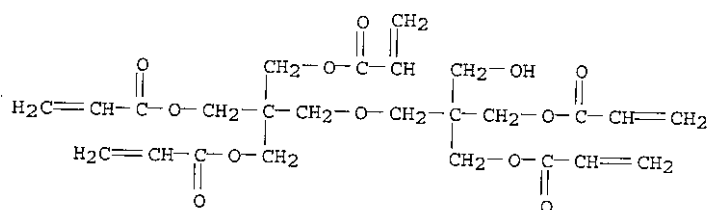
CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 60506-81-2

CMF C25 H32 O12



L22 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2

ACCESSION NUMBER: 2002:429450 CAPLUS
 DOCUMENT NUMBER: 137:13269
 TITLE: Photosensitive composition for lithog. printing plate
 INVENTOR(S): Fujita, Kazuo; Tan, Shiro
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: U.S. Pat. Appl. Publ., 20 pp.
 CODEN: USXXCO

DOCUMENT TYPE: Patent
 LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002068235	A1	20020606	US 2001-970988	20011005
US 6660445	B2	20031209		
JP 2002122989	A2	20020426	JP 2000-312929	20001013
CN 1355448	A	20020626	CN 2000-133306	20001123
JP 2002268219	A2	20020918	JP 2001-69062	20010312
CN 1349132	A	20020515	CN 2001-139305	20011013

PRIORITY APPLN. INFO.: JP 2000-312929 A 20001013
 JP 2001-69062 A 20010312

IT 410100-32-2P

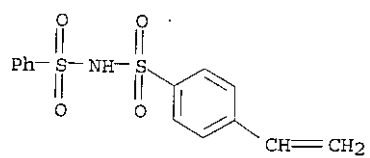
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (photosensitive composition for lithog. printing plate containing)

RN 410100-32-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-(2-methoxyethoxy)ethyl ester, polymer with 4-ethenyl-N-(phenylsulfonyl)benzenesulfonamide and methyl 2-propenoate (9CI) (CA INDEX NAME)

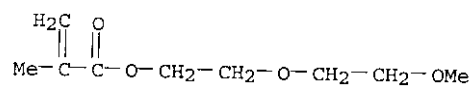
CM 1

CRN 47121-58-4
CMF C14 H13 N O4 S2



CM 2

CRN 45103-58-0
CMF C9 H16 O4



CM 3

CRN 96-33-3
CMF C4 H6 O2

